# Data Sheet

## TEL ACT Clean Track 12 Single Block Tool

- Manufacturer: Tokyo Electron
- Tool Type: Single Block Clean Track
- Model: ACT 12
- Wafer Size: 300mm
- Direction: LEFT HAND SIDE
- Utilized with Nikon S204/205 Scanner Exposure Tool
- General
  iUSC SECSI, SECSII, HSMS, & GEM Interface Compatibility
  3 Blocks Interfaced: Foup-Process Block-Scanner Interface
  3 Wafer Transfer Robot Arms: Foup-Process Block-Scanner Interface
  Control Module on Cassette End-Station (CES) or Foup
- Interface Block
  Single-pincette shared wafer transfer with centering guides
  Standard wafer arm and interface panel to accommodate stepper/scanner
  Interface includes a CPL for insuring consistent wafer temps into the stepper/scanner
- 2 Coaters (COT)
  4 resist nozzles with temperature control
  16 layer resist and solvent filters
  T-100 resist pumps
  4L or 1L Nowpak capability
- 2 Developers (DEV)
  2 “H” nozzles with temperature control per cup
  16 layer developer filter
  Bulk-FSI system for developer
- 2 Adhesion Process Stations (ADH)
  Half sealed chamber with dispersion plate for HMDS
- 5 Chill Plate Process Stations with temperature control (CPL)
- 1 Transfer Chill Plate (TCP)
- 8 Low Temperature Hot Plate Process Stations with temperature control (LHP)
- 4 Precision Chilling Hot Plate Process Stations for SB or PEB (PHP)
- 1 Wafer Edge Exposure Process Station (WEE)
  DUV illumination monitor on lamp housing
  Uses a 250W ultra pressure Mercury lamp with 5x4mm illumination pattern
- Subcomponents
  Fluid Temperature Controller
  Temperature & Humidity Controller
  Chemical Cabinet
  AC Power Box
- Note : Exclude HDD

# Data Sheet

TEL ACT12 Layout

